NOTES:
1. SUBSTRATE MATERIAL:
   FUSED SILICA

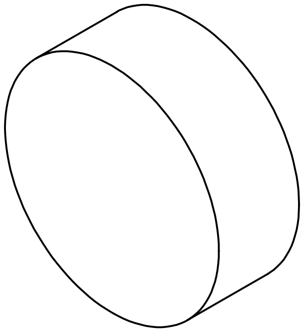
2. COATING (APPLY ACROSS CLEAR APERTURE)
   S1: ULTRAFAST LASER
   Ravg≥99.5% REFLECTIVITY AT 780 - 820nm AT 45° AOI

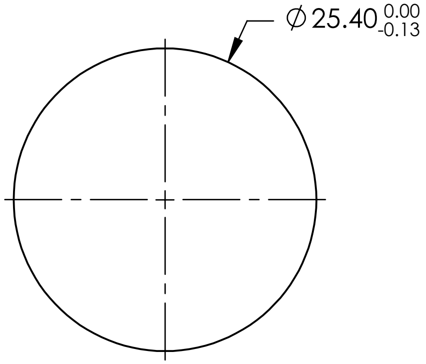
   DAMAGE THRESHOLD, PULSED:
   0.79 J/cm² @ 800nm, 200fs FWHM, LINEAR POLARIZATION, 1 PULSE (TYPICAL)
   0.7 J/cm² @ 800nm, 200fs FWHM, 100Hz, LINEAR POLARIZATION, 1000 PULSES (TYPICAL)

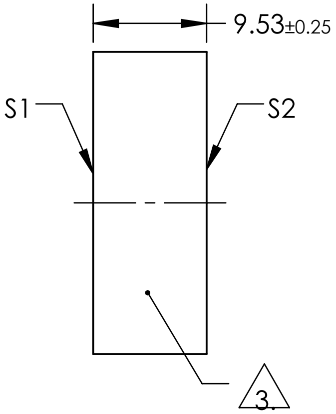
   S2: NONE

△3. FINE GROUND SURFACE

4. RoHS: COMPLIANT







FOR INFORMATION ONLY:
DO NOT MANUFACTURE PARTS TO THIS DRAWING

SPECIFICATIONS SUBJECT TO CHANGE WITHOUT NOTICE
DIMENSIONS ARE FOR REFERENCE ONLY

	S1	S2
SHAPE	PLANO	PLANO
SURFACE ACCURACY AT 632.8nm (P-V)	λ/6	N/A
SURFACE QUALITY	10 - 5	COMMERCIAL POLISH
CLEAR APERTURE	Ø21.59	N/A
BEVEL	PROTECTIVE AS NEEDED	PROTECTIVE AS NEEDED

Edmund Optics®

THIRD ANGLE PROJECTION

TITLE: 800nm DWL 25.4mm DIA. ULTRAFAST HIGH ENERGY MIRROR 45°

ALL DIMS IN: mm

DWG NO: 36409

SHEET: 1 OF 1